

**Amendments to the Claims:**

This listing of claims will replace the listing of claims as pending in the present application:

**Listing of Claims:**

Claim 1 (original): A tantalum sputtering target manufactured by subjecting a molten and cast tantalum ingot or billet to plastic working such as forging, annealing and rolling, wherein the structure of the tantalum target comprises a non-recrystallized structure.

Claim 2 (original): A tantalum sputtering target according to claim 1, wherein the non-recrystallized structure is 20% or more.

Claim 3 (original): A tantalum sputtering target according to claim 1, wherein the non-recrystallized structure is 40% or more.

Claims 4-6 (canceled).

Claim 7 (original): A manufacturing method of a tantalum sputtering target comprising a non-recrystallized structure by subjecting a molten and cast tantalum ingot or billet to processes such as forging, annealing and rolling, wherein plastic working is ultimately performed thereto.

Claim 8 (original): A manufacturing method of a tantalum sputtering target comprising non-recrystallized structure by subjecting a molten and cast tantalum ingot or

billet to processes such as forging, annealing and rolling, wherein, after the ultimate plastic working process, this is further subject to annealing at a temperature of 1173K or less.

Claims 9-12 (canceled).